

# Safety and Tool Contamination Issues When Using Indium Trichloride for Indium Implants in Varian E500 Implanters

Danny Rosenblatt  
Maxim Integrated Products  
NCCAVS Junction Technology Group  
December 10, 2008

# Outline

- InCl<sub>3</sub> procurement and MSDS
- Changing InCl<sub>3</sub> Sources
- E500 In<sup>+</sup> vaporizer source parameters
- Post-indium clean-up implants
- Source and implanter cleanup
- Activation of In implants

# InCl<sub>3</sub> Procurement and MSDS

- Maxim has qualified:
  - Indium Corporation of America
  - American Elements
- Purchased 5 g bottles of InCl<sub>3</sub> for E500
- Inhalation danger: Use respirator at all times. When removing old source, use SCBA. Odor from vaporizer is extremely irritating to lungs (most likely chlorine fumes)
- Eye contact danger: wear safety goggles
- Ingestion danger: wear gloves, change frequently
- Skin contact danger: wear complete bunny suit

# Changing InCl<sub>3</sub> Sources

- Maxim uses W arc chambers, so MoO and MoF contamination is not a concern
- Typical source lasts 3 weeks – run indium 6X a week
- Always have new source ready
- Maxim does not outgas the empty vaporizer
- Source failure almost always occurs after indium implants, when first cleanup implant (B+) is run
- Remove old source
- Clean source bushing thoroughly
- Install new source, pull out vaporizer
- Open 5 g bottle, quickly (but carefully) pour InCl<sub>3</sub> into vaporizer with funnel
- Minimize exposure of InCl<sub>3</sub> to air – it is extremely hygroscopic

# Changing InCl<sub>3</sub> Sources (cont.)

- Quickly install vaporizer and start pumping down source (within 5 minutes of opening InCl<sub>3</sub> bottle)
- Pump down new source for 30 minutes
- Bring up an Ar<sup>+</sup> beam
- Outgas filament
- Condition InCl<sub>3</sub> by heating vaporizer slowly
- Make sure source pressure remains below 5E-5 Torr
- Large burst of water vapor at 80C – 100C as waters of hydration are released
- Continue to heat InCl<sub>3</sub> up to 320C
- Turn off vaporizer, let cool to 100C
- Turn off Ar<sup>+</sup> beam
- Run “Indium Cleanup 1” and “Indium Cleanup 2” recipes (see below for details)
- Return tool to production (In<sup>+</sup>, B<sup>+</sup>, BF<sub>2</sub><sup>+</sup>, As<sup>+</sup>, P<sup>+</sup>)

# E500 In<sup>+</sup> Vaporizer Source Parameters

- InCl<sub>3</sub> vaporizer temperature: 320C
- Arc voltage: 60 V
- Arc current: 500 mA
- Extraction voltage: 40 kV
- Source magnet current: 20 A
- Setup cup current: 115 uA
- Integrated beam current: 75 uA
- Beam width: 35 mm

# Post-Indium Clean Up Implants

- Derived from various Varian BKM and IIT papers and Maxim experiments
- Cool vaporizer from 320C to < 100C (20 min)
- Indium Clean #1: Implant 25 dummy wafers with B11,  $1.50E14$ , 150 keV, 400 uA integrated beam current, 50 scans, total time 25 min
- Indium Clean #2: Implant the same dummy wafers with As75,  $2.00E14$ , 80 keV, 350 uA integrated beam current, 100 scans, total time 45 min
- Total cool down and clean up time is 90 minutes
- Effectiveness of clean up implants judged by parametric test data, not analytical data
- Clean up requirements may be different for every technology at every company!

# E500 Source Cleanup

- Place source in exhausted fume hood
- Remove slug from  $\text{InCl}_3$  vaporizer
- Clean vaporizer with wipes and isopropyl (no water!)
- Clean arc chamber – additional black flakes are present from indium operation
- Maxim does not use an oven to bake the clean vaporizer
- Dispose of indium waste along with As, B, P waste
- Place all implant waste in 55 gallon drum
- Waste disposal company picks up waste

# Activation of In Implants

- Solid Solubility of B in Si:  $1E21 \text{ cm}^{-3}$
- Solid Solubility of In in Si:  $4E17 \text{ cm}^{-3}$
- Rules out In for USJ for S/D and SDE
- In is useful for VtN and NHALO implants
- These are shallow but lightly doped
- Can improve short channel effect starting at 180 nm technology